

## Introduction of MEMS technology with the ceramic mold for Next-Generation test probes

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Point Engineering



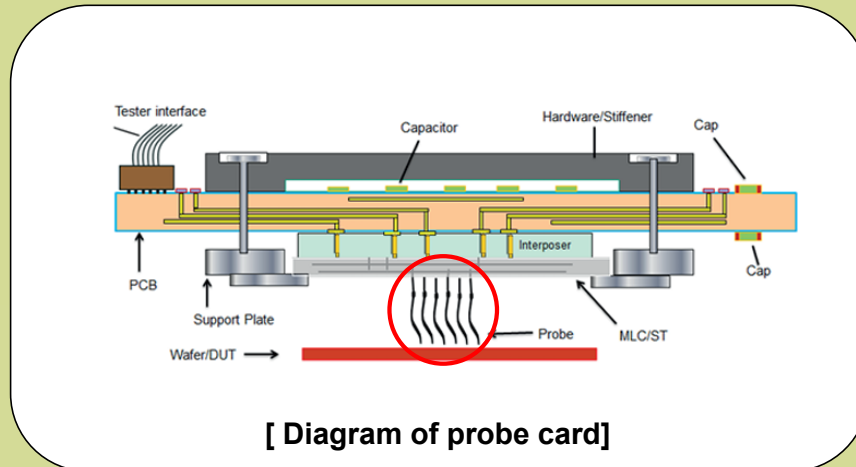
## Contents

- Technology Trend
- Bridging the gap
- Suggestion : New tools for MEMS
- Fabrication case / Measurement Results
- Conclusion

## Test Pin Application Areas

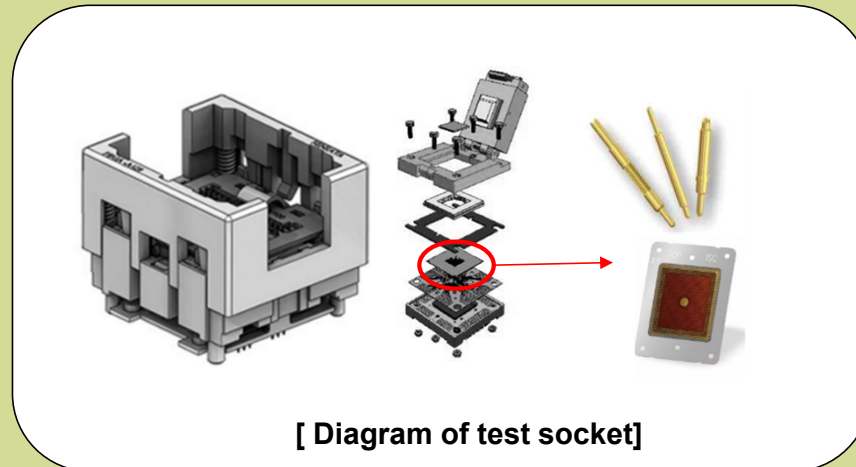
- MEMS pins with high performance can be built to customer specifications for probe cards and test sockets applications

### 1. Probe Card (for Wafer Test) – Probe Pin



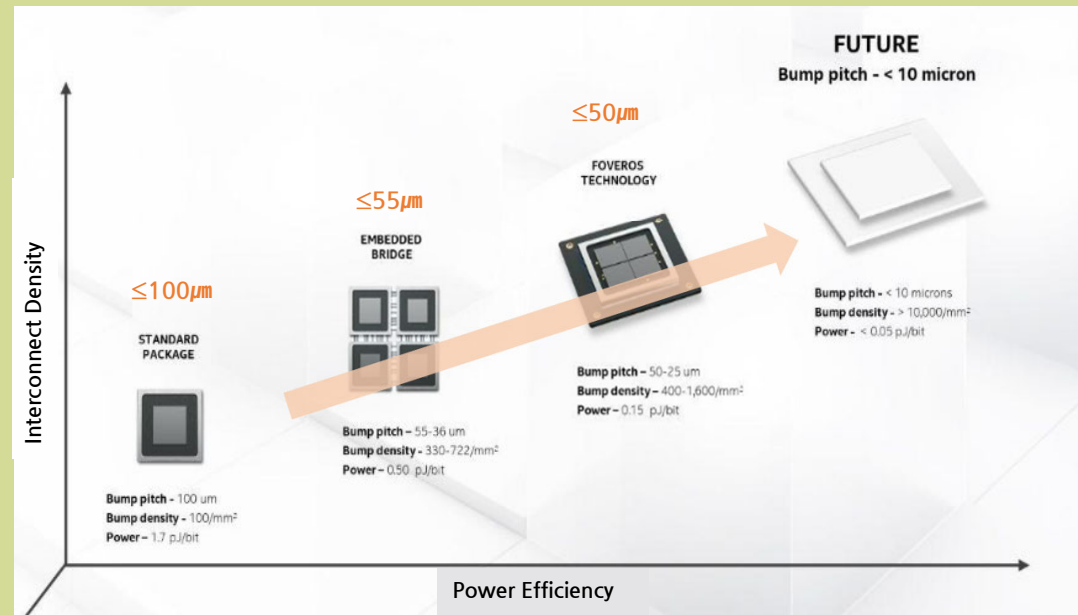
Source: Informacije Midem, Vol.46, No.2

### 2. Test Socket (for Package Test) – Socket Pin



## Technology Trend

- There is still a need for new solutions that can respond to Fine-pitch, High-speed, and High-density requirements.



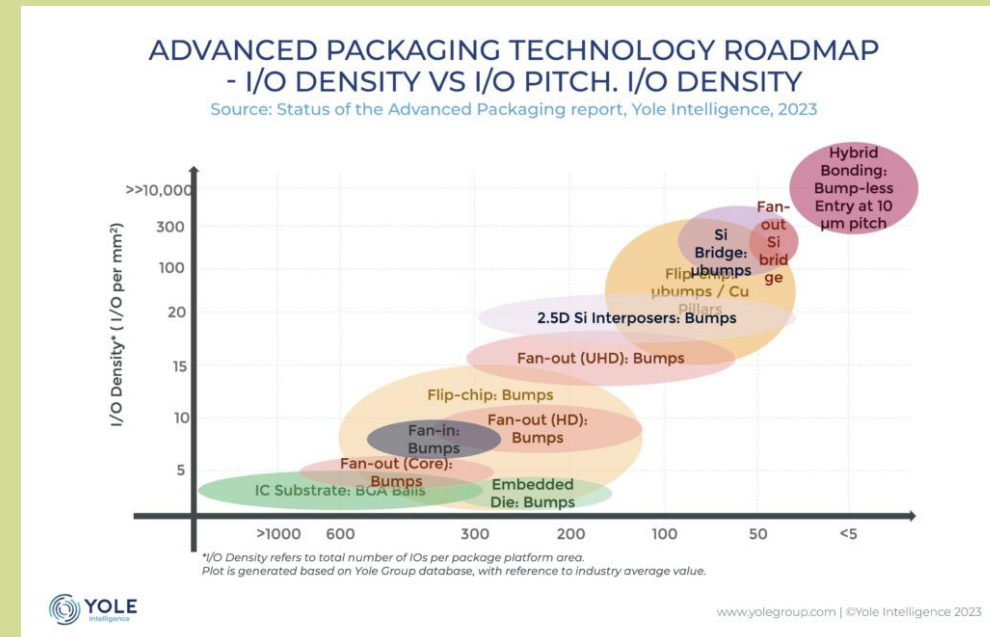
Source: <https://www.intel.com/content/>

## Technology Trend

- As packaging technology is segmented & evolves
- Demands for probes are also being divided based on application
- Requirements

• More computing power	• System integration
• Higher speed	• More sensors
• More bandwidth	• More memory
• Lower latency	• Lower cost
• Lower power	• Hardware-software compatibility
• More functionality	

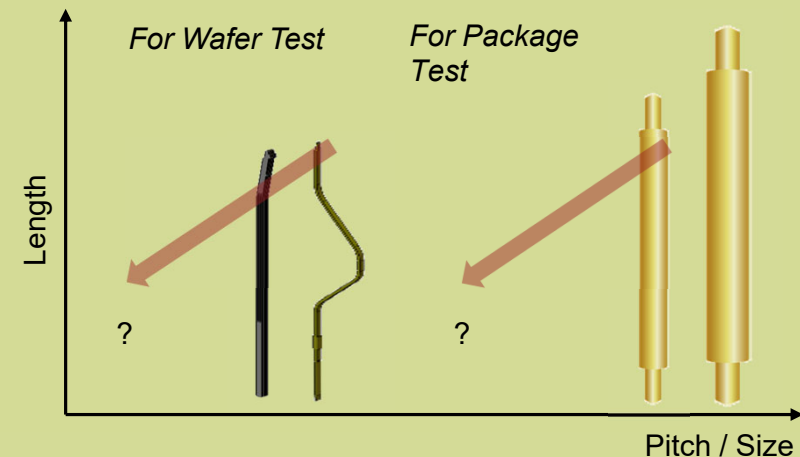
Source: Yole



Source: Yole



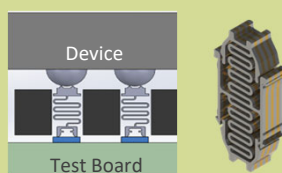
## Technology Trend

- Limitation of existing MEMS needle
  - 1) Long production time
  - 2) High cost
  - 3) Limitations in thickness  
(hard to get >100um thickness)
  - 4) Still needs for MEMS fabrication technology to make probes finer, shorter



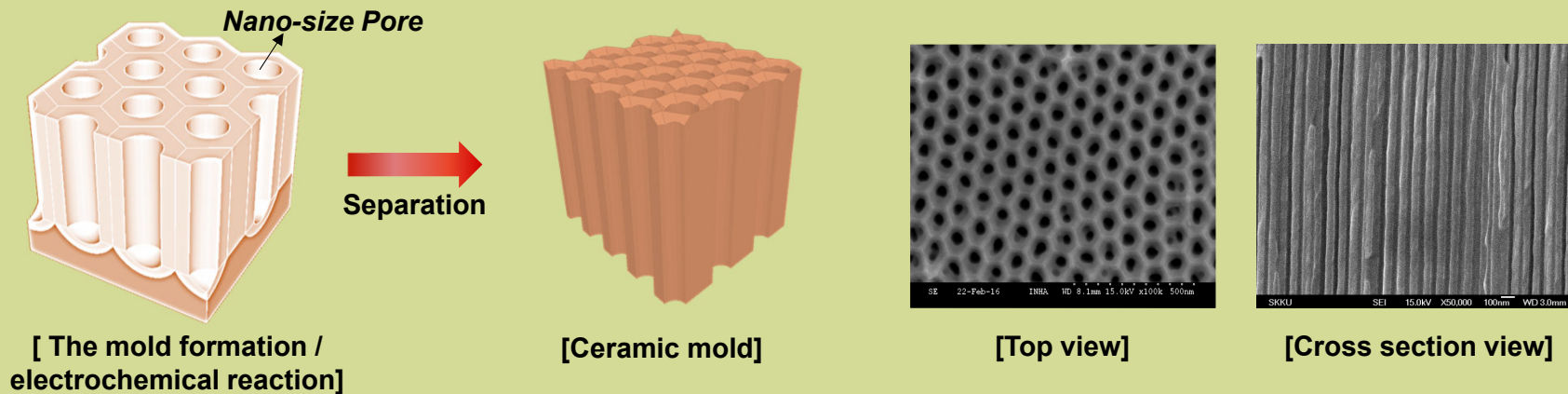
## Bridging the gap

- MEMS probes satisfying high frequency, short length with fine patterning could be formed

	Pogo Type	Rubber Type	PEC MEMS socket
			
<b>Size / Pitch</b>	Wide range of pitches Long Length (high inductance)	Short Length (low inductance)	<b>Fine Pitch with Short Length</b> ( $\leq 0.3\text{mm}$ Pitch, $\geq 0.65\text{mm}$ Length)
<b>Precision / Manufacturing</b>	High precision (contact tip) Price & manufacturing time $\uparrow$	Price & manufacturing time $\downarrow$ Manufacturing price & time $\downarrow$	<b>Fine Patterning, High Precision</b> Fabrication difficulty & Manufacturing time $\uparrow$ No Assembly
<b>High frequency / Signal loss</b>	High speed & frequency Durability, Longevity $\uparrow$	Thermal durability, Longevity $\downarrow$	<b>High speed &amp; frequency</b> Durability, Longevity $\uparrow$

## Suggestion : New tools for MEMS

- PEC's distinguished "Ceramic mold applied MEMS technology"
  - Replacement of pre-existing PR mold with the Ceramic mold





## Suggestion : New tools for MEMS

- Properties of PEC's Ceramic mold



### 1. Mechanical

- Highly Flexible and Bendable

### 2. Thermal

- Low thermal conductivity
- Low thermal expansion

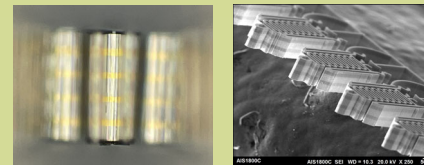
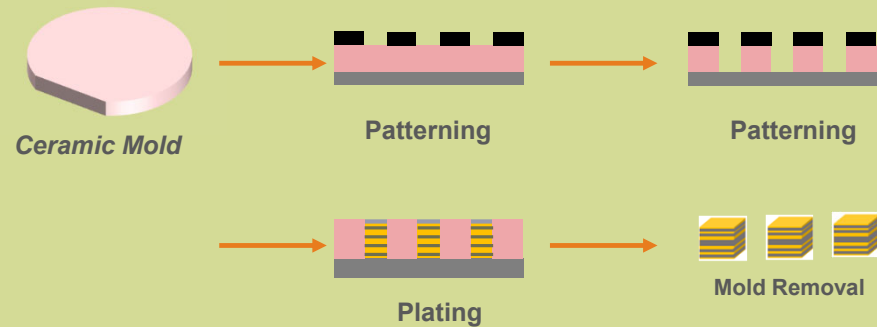
### 3. Electrical

- Dielectric Strength
- Low Permittivity

Bending Strength(Mpa)	810
Young's Modulus(Gpa)	110
Thermal Conductivity(W/mk)	2.197
Thermal Expansion(x10 <sup>-6</sup> )	1.5~3.78
Dielectric Strength	>50x10 <sup>6</sup>
Permittivity	3.7~4.5

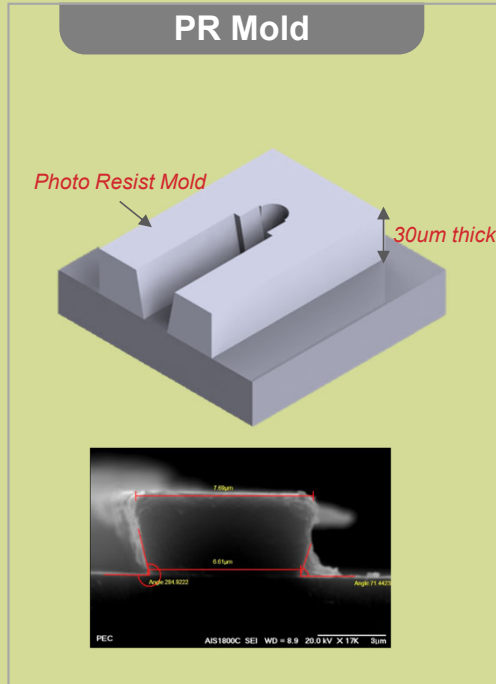
## Suggestion : New tools for MEMS

- MEMS Process using PEC Ceramic mold



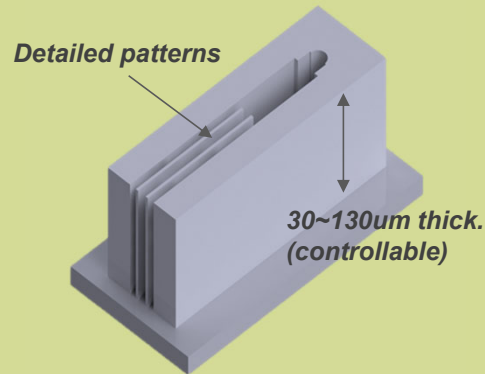
## Suggestion : New tools for MEMS

### PR Mold



### Ceramic mold

#### MEMS Process with PEC Ceramic mold



[Image of PEC's Ceramic wafer]



- Complex patterns with minimum 5um gaps can be stably implemented
- Top-Bottom dimension tolerance : max 1.5um (@ >100um thickness)



Enable MEMS



Corrosion Resistance



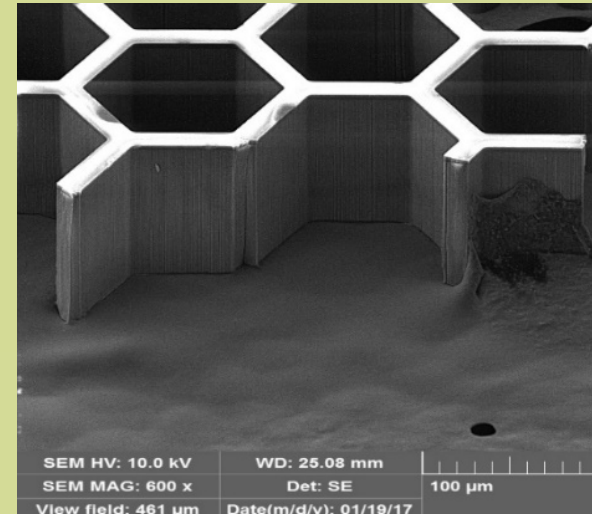
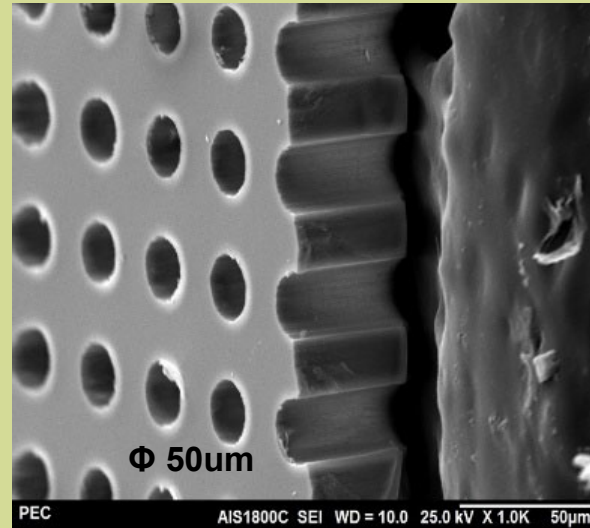
Thermal Resistance



Stable Dimension

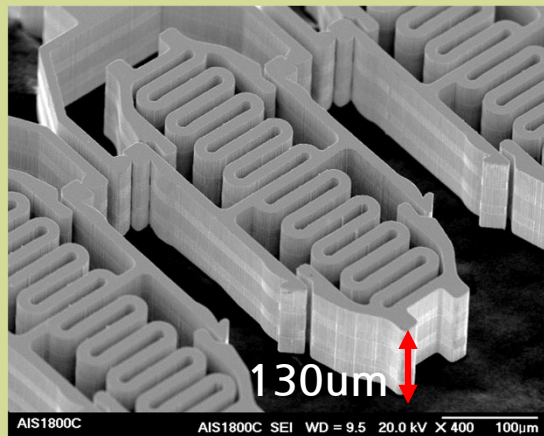
## Suggestion : New tools for MEMS

- Image of patterned ceramic mold

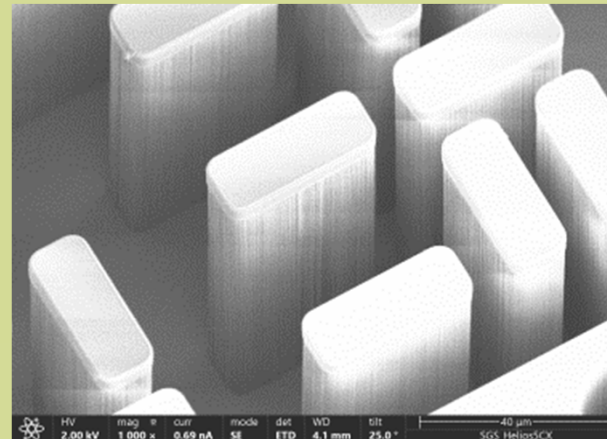


## Suggestion : New tools for MEMS

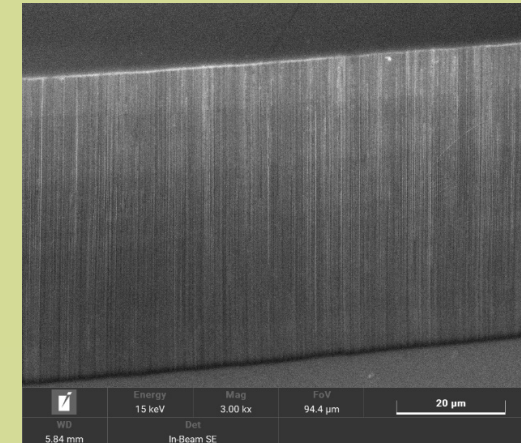
- The ceramic mold enables to straightened probe manufacturing with desirable thickness (up to 130um)



Fabricated socket probes using the mold

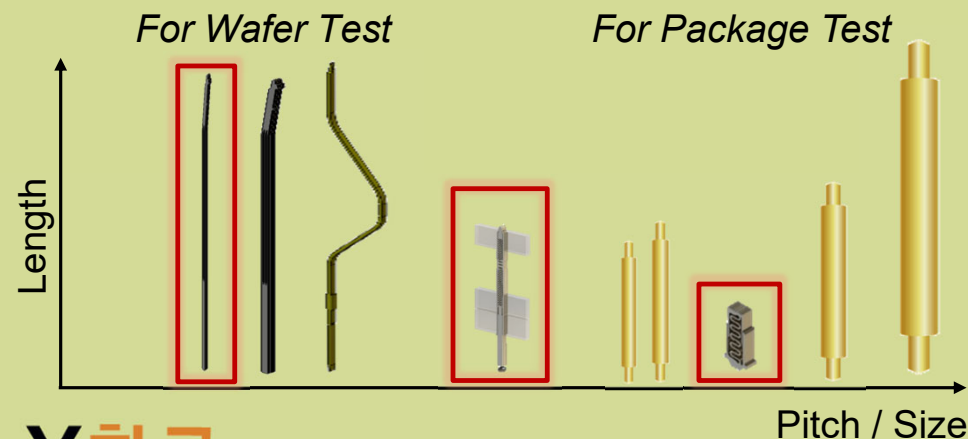


Fabricated ceramic mold with thickness



## Suggestion : New tools for MEMS

- Shorter probe length while maintaining pattern & shape
- This advantage point can be applied to
  - 1) Fine pitch MEMS buckling with high C.C.C
  - 2) Short length MEMS vertical spring pin with relatively high current
  - 3) Short & thick MEMS Pogo probe for RF test solution





## Development & Fabrication case

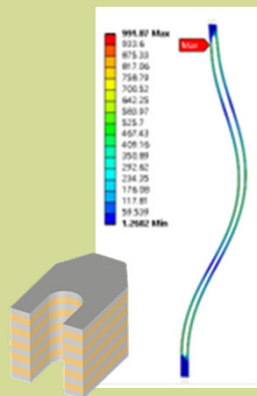
- Probes fabricated with ceramic molds have relatively more volumes which enables probes to carry more C.C.C in same dimension

### Comparison between

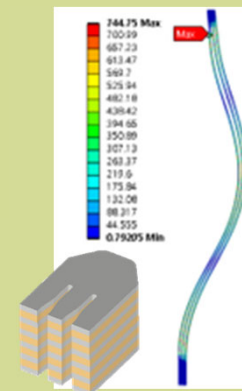
Conventional MEMS needle

vs

Ceramic Mold MEMS needle



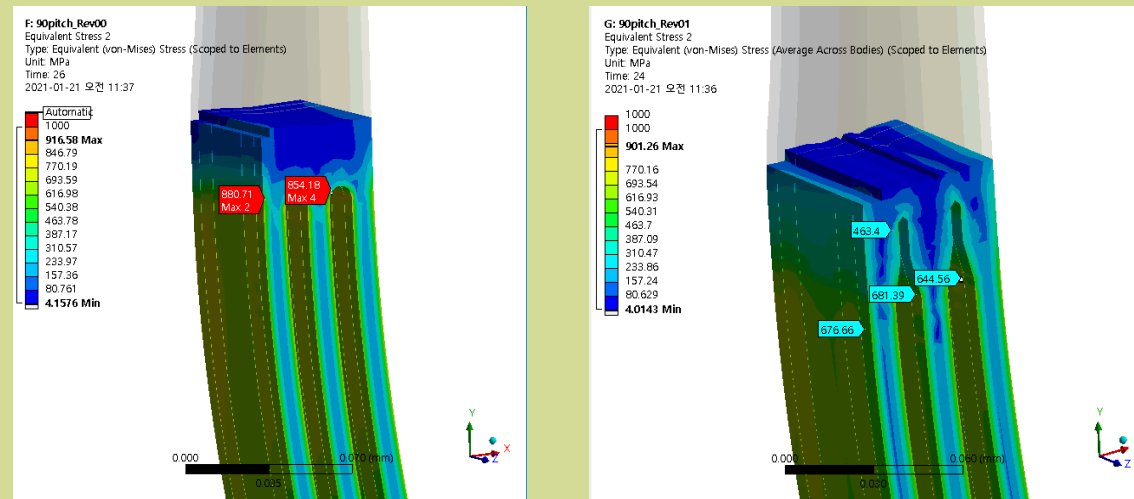
- Needle dimension : 55 X 55 X 4,400  $\mu\text{m}$
- Volume:  $4.67 \times 10^6 \mu\text{m}^3$
- Predicted C.C.C: 1.18A
- Max Stress: 991MPa



- Needle dimension : 55 X 55 X 4,400  $\mu\text{m}$
- Volume:  $4.96 \times 10^6 \mu\text{m}^3$  (6% higher)
- Predicted C.C.C: 1.40A (19% higher)
- Max Stress: 744MPa (25% less)

## Development & Fabrication case

- **Fine slit structure for stress relief**
  - With accurate & precise fabrication, fine slit structure can be implemented on probe needle to reduce probe stress and increase life span

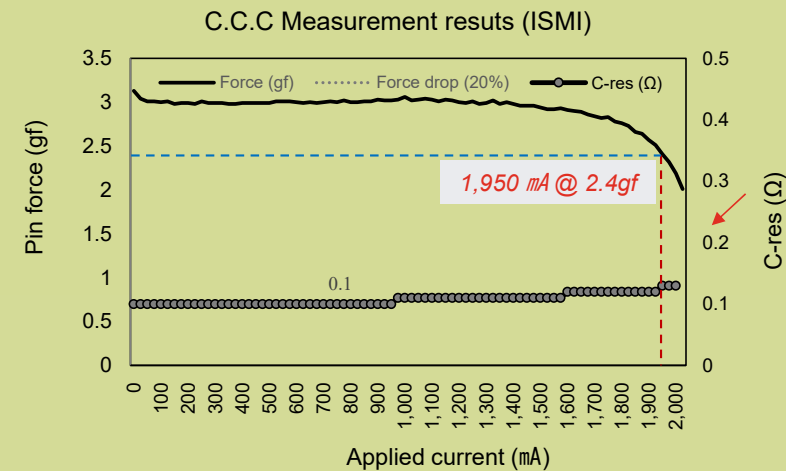
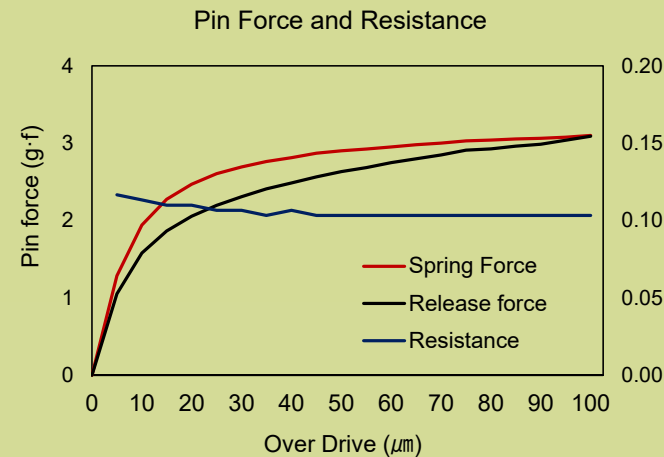
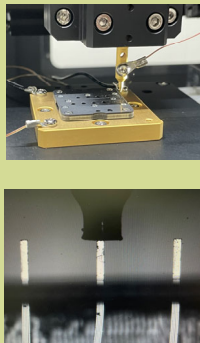


Comparison of stress between the conventional & fine slit structure manufactured with ceramic mold



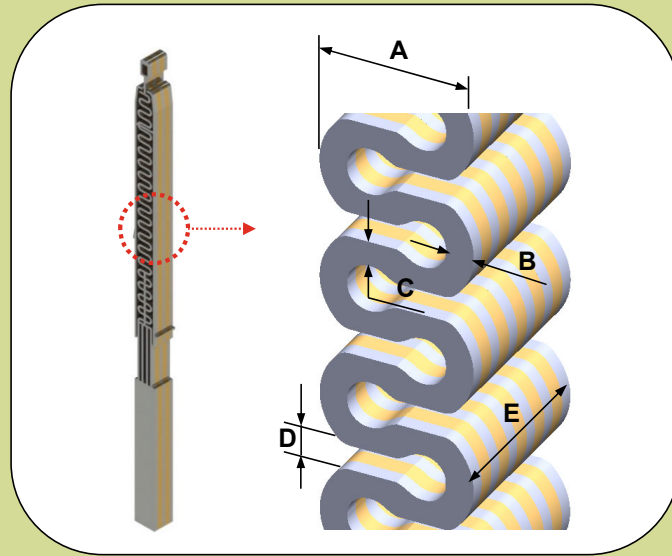
## Development & Fabrication case

- **Mechanical & Electrical performances of 110um pitch model**
  - Low resistance was maintained within O.D 100um range
  - High C.C.C through designs of Low resistance (material, structural)

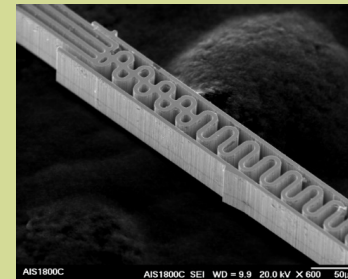
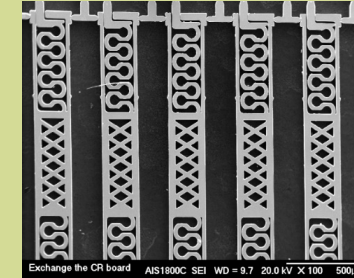
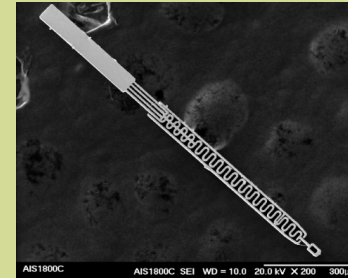


## Development & Fabrication case

- Design Rule of Point spring structure

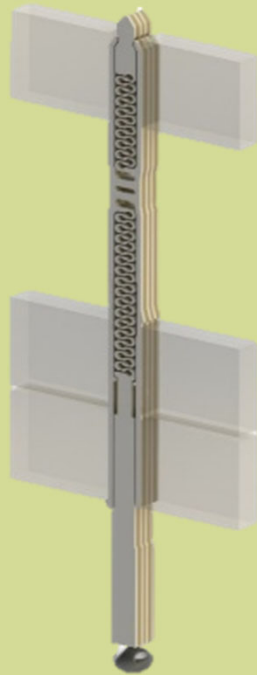


A	B	C	D	E
≥ 50	≥ 5	≥ 5	≥ 5	< 150



## Development & Fabrication case

- Unique MEMS vertical probes with spring structure



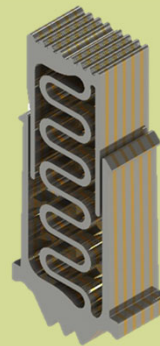
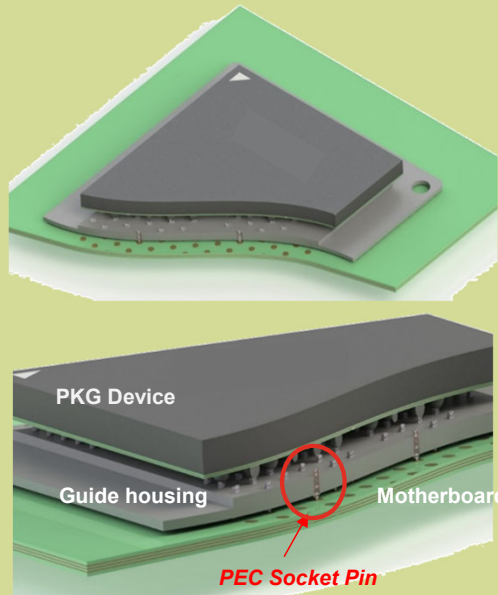
Parameters	Specification
Pitch	150 $\mu$ m
Probe Dimension	Thickness 80 $\mu$ m
Probe Length	1.6mm
Recommended stroke (Full Stroke)	150 $\mu$ m (200 $\mu$ m)
Contact force	3.0gf
Max. Current (ISMI )	~2,000mA
Contact Resistance	0.1 $\Omega$

- Straightened probe structure
- Solution for 110~150 $\mu$ m pitch
- Carry relatively high current



## Development & Fabrication case

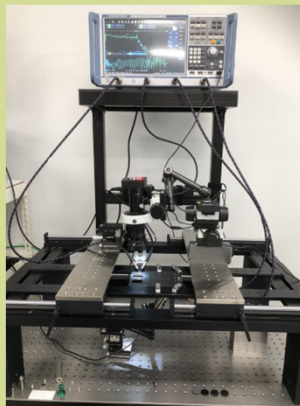
- Extremely short and thick MEMS sockets



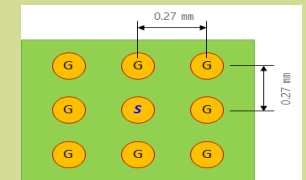
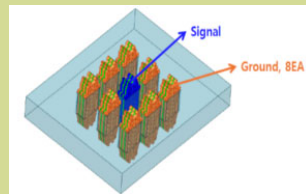
Parameters	Specification
Pitch	>270 $\mu$ m
Probe Dimension	Thickness 130 $\mu$ m
Probe Length	< 650um
Contact Force	5~15gf
Max. Current (ISMI )	1,000mA
Contact Stroke	50~150um
Frequency	100GHz@-1dB

## Development & Fabrication case

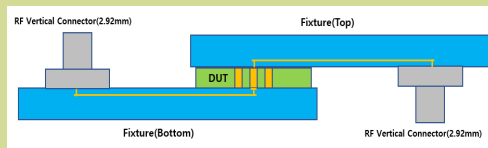
- Frequency test result of PEC MEMS socket pin



[Measurement Device - ZNB40]

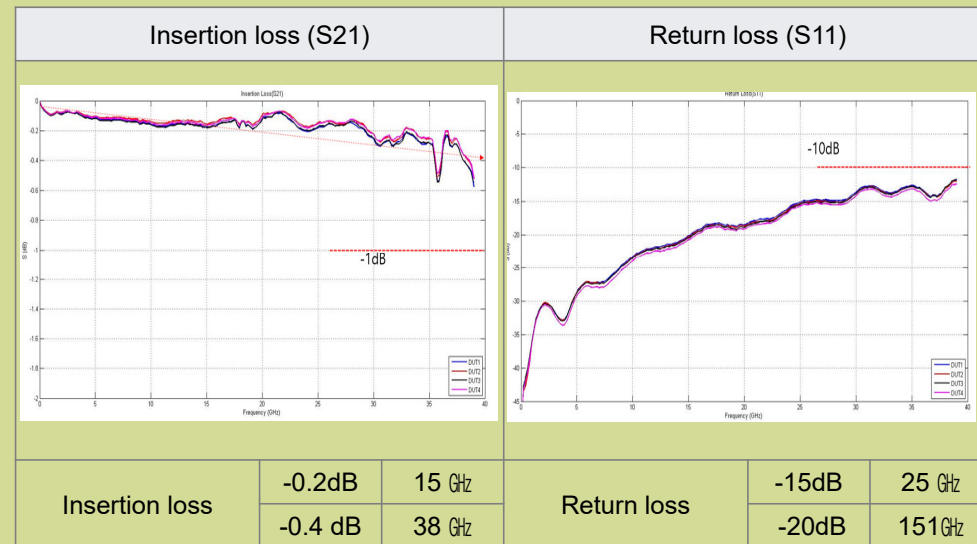


[Diagram of DUT Array Data]



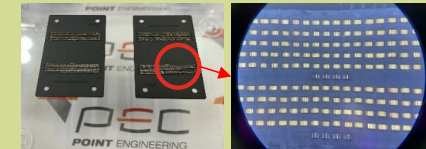
[Diagram of DUT Fixture]

[ Insertion / Return loss Measurement Results ]



## Development & Fabrication case

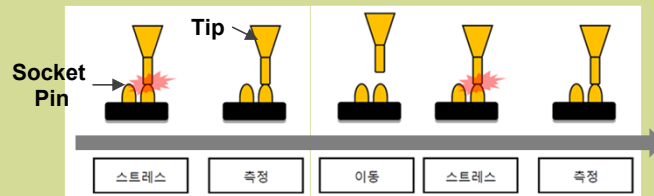
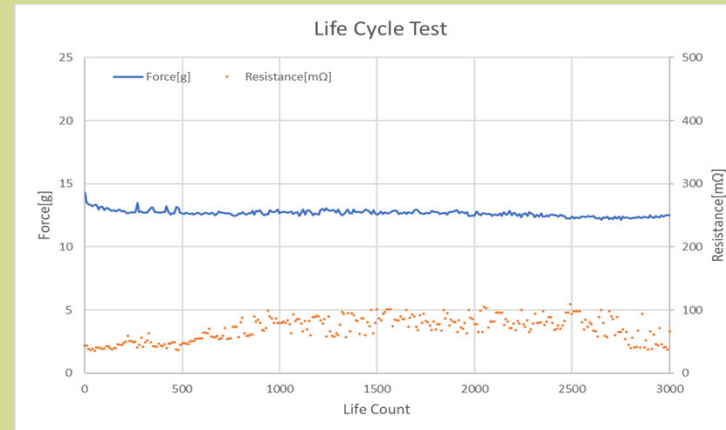
- Reliability test result of PEC MEMS socket pin



[MEMS Socket Pin Module for the Test]



[Test Device – SDS2000]



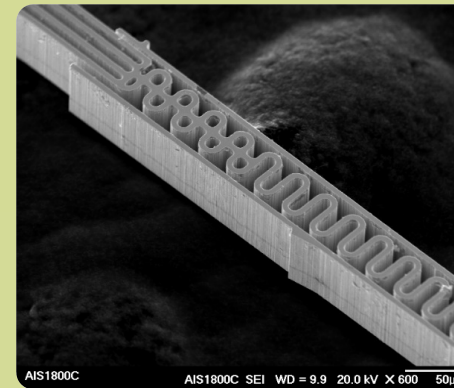
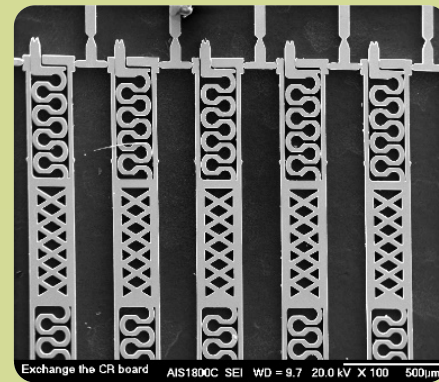
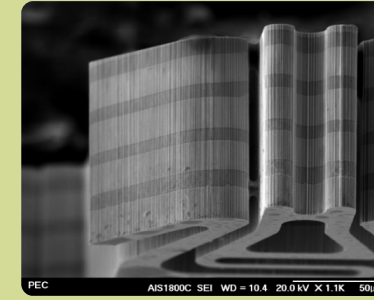
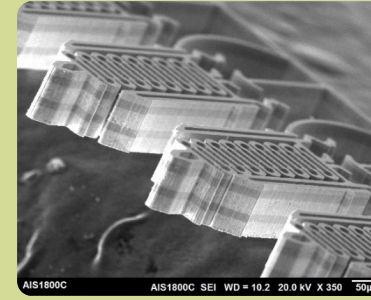
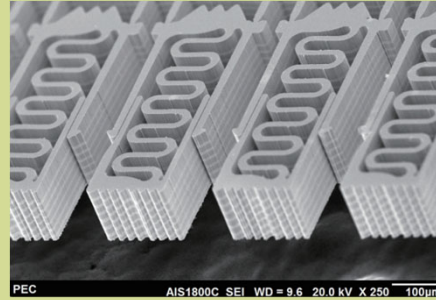
[Diagram of repeatedly contact test]

➔ During 3K repeated contact test...

- ≤1% Force drop during 3K touch down test
- ≤100mΩ Contact resistance changes



## Design flexibility of AAO MEMS Solution



## Conclusion

- Customized test pins upon requests as well as churning out MEMS pins for wafer-level testing and socket pins for packaging testing.
- Using distinguished PEC ceramic mold, probes with thickness, short length and fine patterned could be stably fabricated.
- Satisfying emerging packaging technologies' requirements of high density, high frequency, high speed, and stability through our MEMS element technology.



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